



(51) International Patent Classification:

G01N 33/18 (2006.01) B08B 3/12 (2006.01)
H01L 21/02 (2006.01)

(21) International Application Number:

PCT/EP2011/072639

(22) International Filing Date:

13 December 2011 (13.12.2011)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

2010-283078 20 December 2010 (20.12.2010) JP

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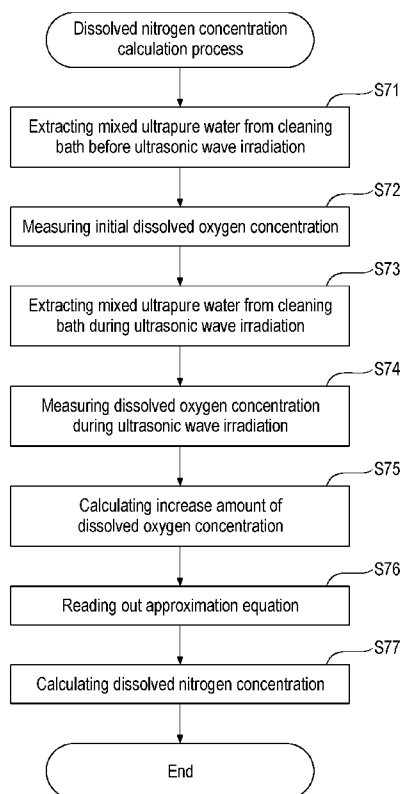
(81) Designated States (unless otherwise indicated, for every
kind of national protection available): AE, AG, AL, AM,
AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ,
CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO,
DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN,
HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR,
KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME,
MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ,
OM, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SC, SD,
SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR,
TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every
kind of regional protection available): ARIPO (BW, GH,
GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, SZ, TZ,

[Continued on next page]

(54) Title: DISSOLVED NITROGEN CONCENTRATION MONITORING METHOD, SUBSTRATE CLEANING METHOD,
AND SUBSTRATE CLEANING APPARATUS

Fig. 7



(57) Abstract: There is provided a dissolved nitrogen concentration monitoring method that enables real-time accurate monitoring of the dissolved nitrogen concentration of a cleaning liquid without complicated operations as well as cost reduction. A dissolved oxygen concentration D_{O_2} during ultrasonic wave irradiation is measured by a dissolved oxygen concentration meter 43. An increase amount of dissolved oxygen concentration ΔD_{O_2} is calculated by subtracting an initial dissolved oxygen concentration D_0 from the measured dissolved oxygen concentration D_{O_2} . Subsequently, an approximation equation corresponding to a specific overflow rate or ultrasonic output power level is read out from a storage section 46, and the approximation equation read out from the storage section 46 is used to calculate a dissolved nitrogen concentration D_{N_2} of mixed ultrapure water from the increase amount of dissolved oxygen concentration ΔD_{O_2} .



UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

— *with international search report (Art. 21(3))*